SG-07
www.oxfordplasma.de/process/sige_bo.htm

OXFORD INSTRUMENTS

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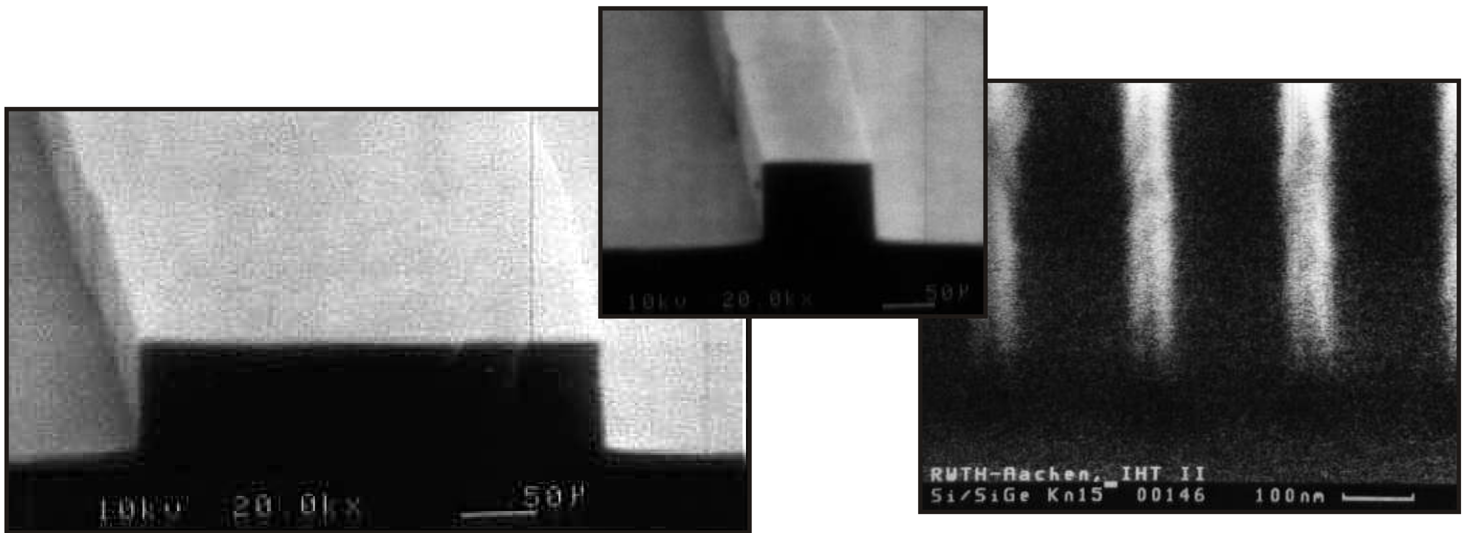
Plasmalab Data

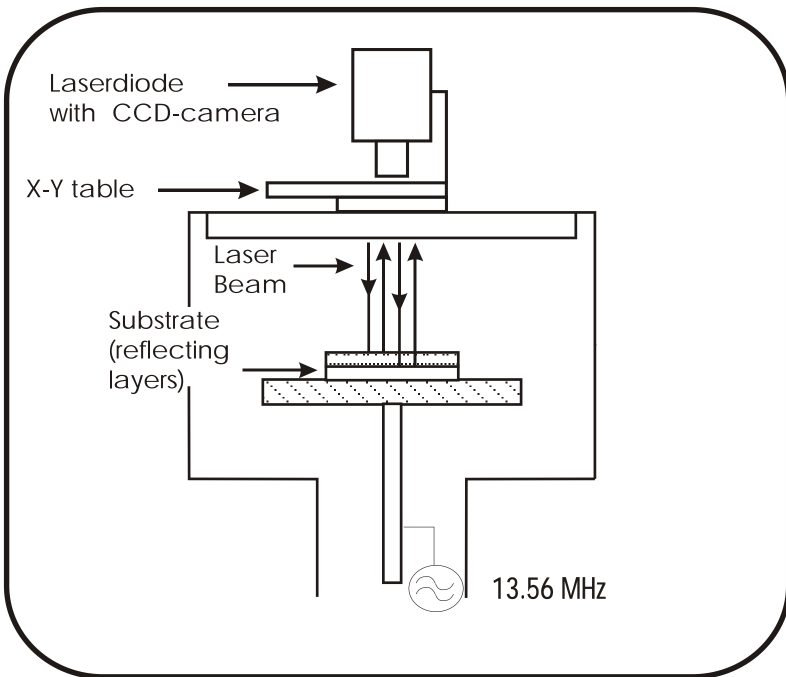
Si / SiGe / Si Heterostructure RIE using Laser Interferometry

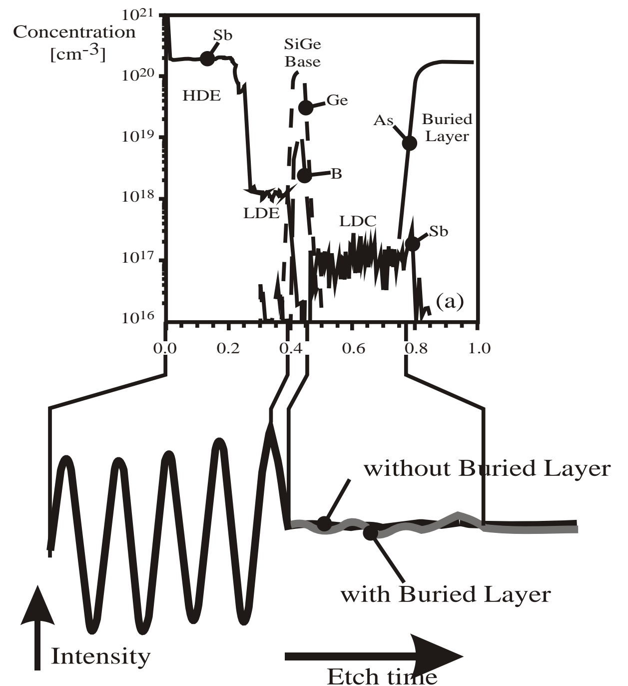


Courtesy of the Ruhr University Bochum
Lehrstuhl für Elektronische Bauelemente
(left SEM's and laser signal)
Anisotropic F Etching into a
Si / SiGe / Si Heterostructure
Rate ca 100 nm / min

Plasmalab System 100
Plasmalab System 133
Plasmalab 80 Plus

Courtesy of the RWTH Aachen
Institut für Halbleitertechnik II
Rate 110 nm/ min
Trilevel Resist Mask
Anisotropic, residue free etch
smooth walls
aspect ratio: 5 - 10





RIE System with laser interferometer through top electrode and the laser signal intensity versus time